



PATENT
Attorney's Docket No. 015675P326

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#10/B
Jude
6/27/02

In re Application of:)

Andre Leycuras)

Serial No.: 09/601,109)

Filed: October 16, 2000)

For: CHEMICAL VAPOR)
DEPOSITION REACTOR AND)
PROCESS)

Examiner: Bret P. Chen

Art Group: 1762

Assistant Commissioner for Patents
Washington, D.C. 20231

AMENDMENT AND RESPONSE TO OFFICE ACTION

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Sir:

In connection with the Request for Continuing Examination under 37 CFR §1.114,
Applicant respectfully requests entry of the following amendments and reconsideration in view of
the following remarks.

IN THE CLAIMS

Presented below are all the amended claims in clean unmarked form. The claims, in
marked-up form, are presented as an attachment.

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JUN 26 2002
TC 1700

- 1 1. (Amended) Process for a chemical vapor deposition of layers of a material on a
2 substrate which extends generally in a plane, comprising:
3 placing the substrate in a horizontal duct made of a refractory material;
4 heating independently an upper and lower wall of the duct by a first and second heater, the
5 first and second heater extending above and below the substrate, outside the duct;
6 heating independently an upper and lower surface of the substrate by radiation of heat from
7 at least one wall of the duct raised to a temperature substantially higher than ambient temperature;